



**HITACHI M712 / M711 Dry Etch process chamber
Vintage 2006 300mm**

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Location warehouse Nijmegen condition "As is"

Manufacturer: HITACHI

Type: 300mm M712 / M711 Etch chamber

Date of manufacture: 2006

Software revision: 1.07 PMv.02.16M

Configuration:

Dry Etch Chamber, 12"

ESC Type: Bipolar

Endpoint type: Hitachi EPD monitor ePMv02.16M

SHIMAZU EC TMP

3203LMC-K1 EC TMP Controller

DAIHEN ES7-IIA EC Source generator

PEARL CF-500-400K EC Bias generator

Gas configuration:

Line / EC1 / Strip

1 / Ar

2 / C12

3 / SF6

4 / HBr

5 / CF3

6 / CH4

7 / NF3

8 / O2

9 / N2

10 / SF6

11 / C12

12 / O2



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